FORM PTO - 1449	ATTORNEY DOCKET NO.: IBX-005
INFORMATION DISCLOSURE STATEMENT	APPLICANT(S): Card et al.
	SERIAL NO.: 10/621,532
	FILING DATE: 7/17/03 GROUP: Not yet assigned

U.S. PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
TS	A1	5,467,883	11/21/95	Frye et al.	216	60	11/27/93
TS	A2	5,559,690	9/24/96	Keeler et al.	364 700	164 24	9/16/94
TS	A3	5,654,903	8/5/97	Reitman et al.	364 702	551.01	11/7/95
TS	A4	5,740,033	4/14/98	Wassick et al.	364 700	149 27	10/13/92
TS	A5	6,268,226	7/31/01	Angell et al.	438	16	6/30/99

FOREIGN PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
TS	B1	WO 01/57605	8/9/01	WO	G05B	13/04	1/11/01	N	Y
TS	B2	DE196 37 917 A1	3/19/98	DE	G05B	13/04	9/17/96	Y	

OTHER ART, JOURNAL ARTICLES, ETC.

EXAM. INIT.		OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)
TS	C1	Card et al., "Dynamic Neural Control for Plasma Etch Process," IEEE Transactions on Neural Networks, (1997). pg. 1-18
TS	C2	Dillon et al., "Guest Editorial Everyday Applications of Neural Networks," IEEE Transactions on Neural Networks, 8:4 (July 1997). 825- 826
TS	C3	Hatzipantelis et al., "Comparing Hidden Markov Models with Artificial Neural Network Architectures for Condition Monitoring Applications," Artificial Neural Networks, 26-28, Conference Publication No. 409 (June 1995). r. 1-6
TS	C4	Kim et al., "Intelligent Control of Via Formation by Photosensitive BCB for MCM-L/D Applications," IEEE Transactions on Semiconductor Manufacturing, 12:503 (1999). pg. 1-13
TS	C5	Konstantopoulos et al., "Controllers with Diagnostic Capabilities. A Neural Network Implementation. Journal of Intelligent and Robotic Systems," Department of Electrical Engineering, University of Notre Dame, IN 12: 197-228 (1995).
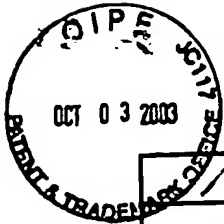
/	C6	Lada et al., "A Wavelet-Based Procedure for Process Fault Detection," (September 17, 2001). pg. 1-30
TS	C7	Moyne, "AEC/APC Vision: A Research and Suppliers' Point of View," 3rd Annual European AEC/APC Conference Proceedings (2002). pg. 1-25
TS	C8	Rietman et al., "A Study on $\mathfrak{R}^m \to \mathfrak{R}^1$ Maps: Application to a 0.16-μm Via Etch Process Endpoint," IEEE (2000). pg. 457-468
TS	C9	Rietman et al., "A System Model for Feedback Control and Analysis of Yield: A Multistep Process Model of Effective Gate Length, Poly Line Width, and IV Parameters", IEEE (2001). pg. 32-46
TS	C10	Rietman, "Neural Networks in Plama Processing," Journal of Vacuum Science and Technology: Part B, IEEE Transactions on Semiconductor Manufacturing, 14:1 (2001). 508-510
TS	C11	Smyth et. al., "Hidden Markov Models an Neural Networks for Fault detection in Dynamic Systems," California Institute of Technology (1993). pg. 582-591
TS	C12	Zhang et al, "Control of Spatial Uniformity in Microelectronics Manufacturing: An Integrated Approach," Proceedings of AEC/APC (2000). pg. 1-38

EXAMINER /Thomas Stevens/ (09/13/2006)	DATE CONSIDERED 09/13/2006

2682896_1